

# Robust electron sources for future accelerator facilities

Jyoti Biswas

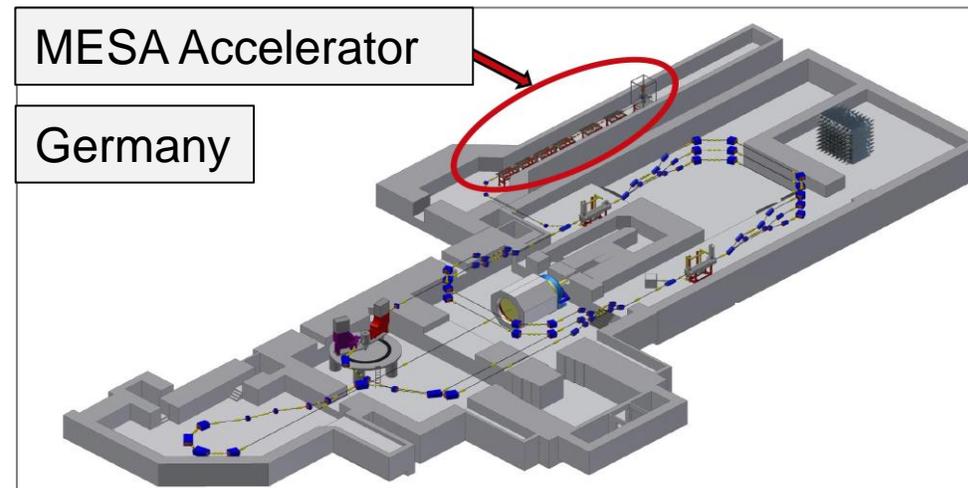
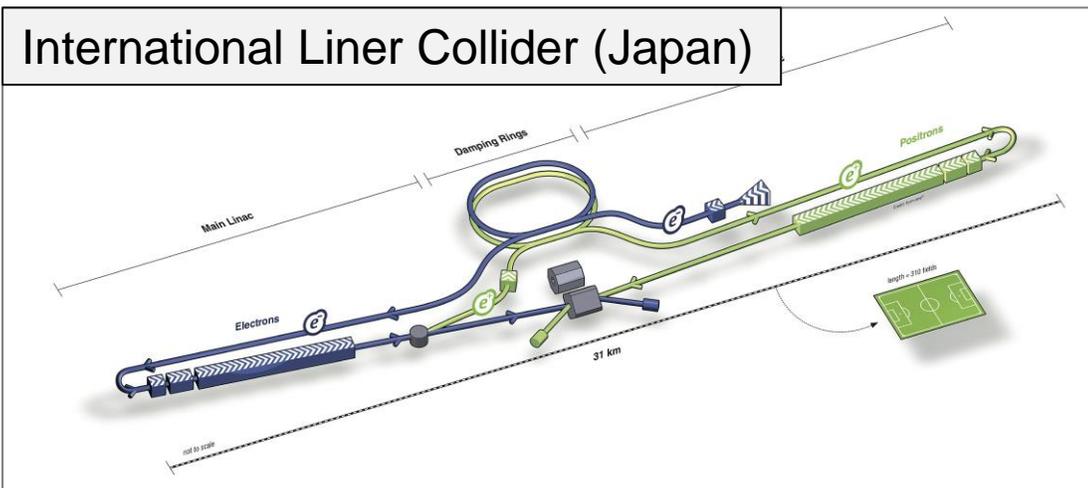
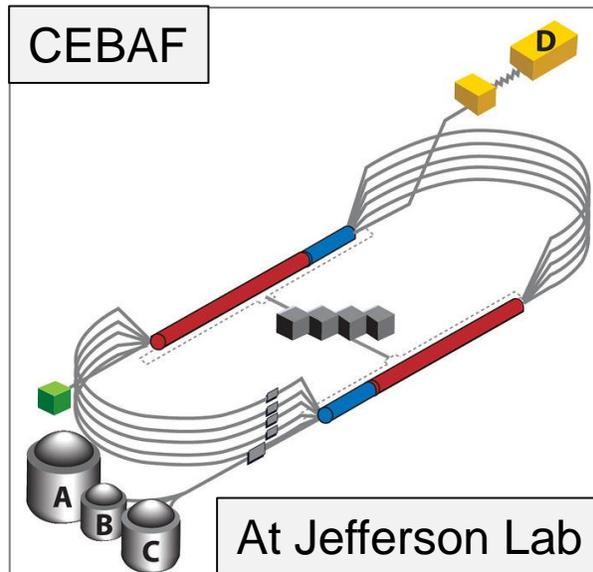
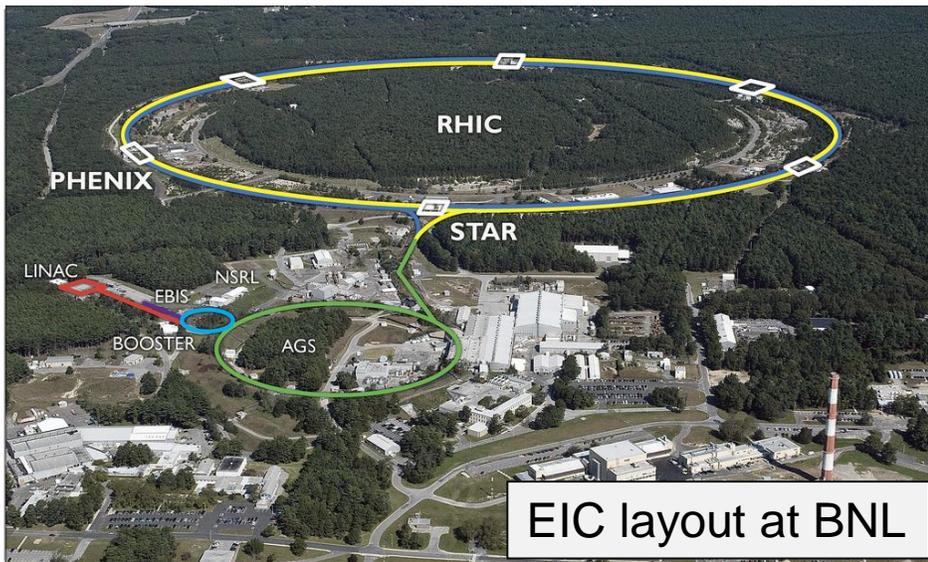
Brookhaven National Laboratory  
On behalf of the collaborations

May 23, 2023

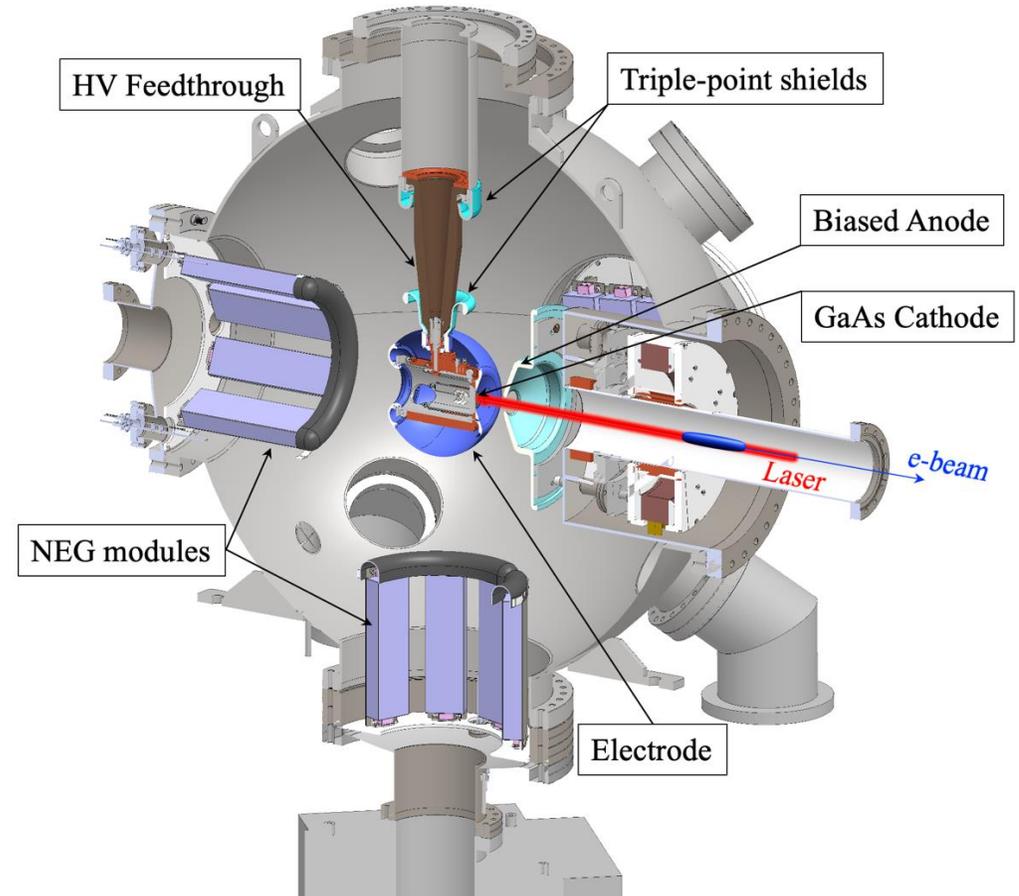
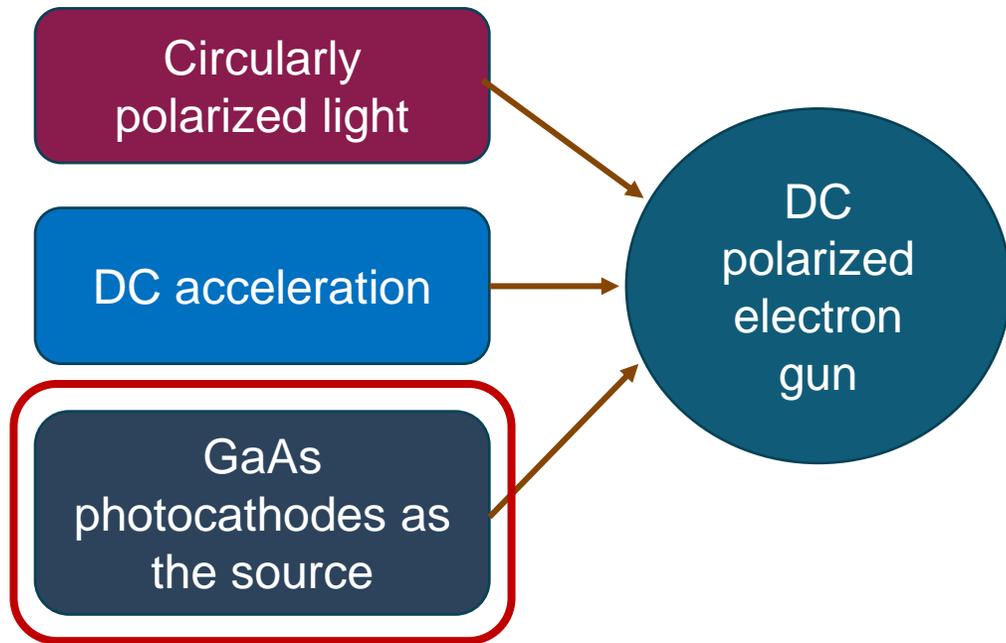


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# Perspective - Polarized Electron Sources



# DC - Polarized Electron Sources



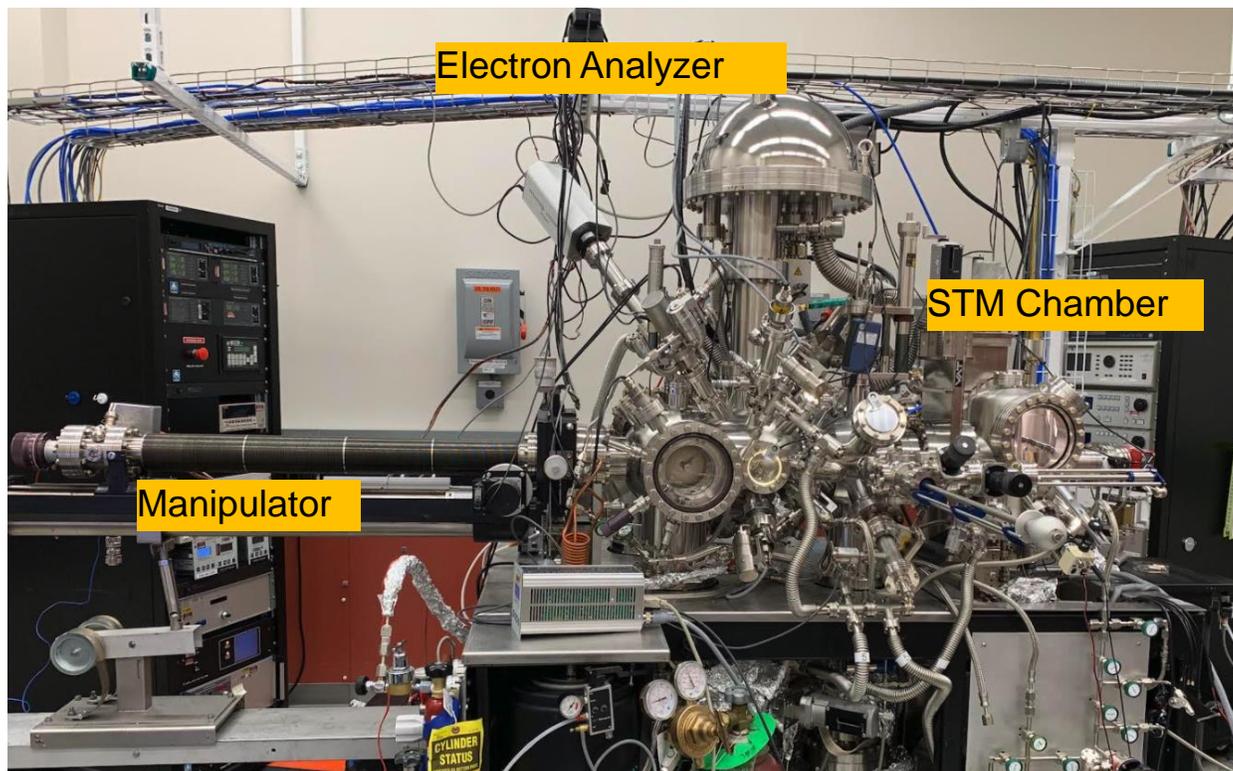
# Polarized Electron Sources

## GaAs-based photocathodes: Essential Attributes

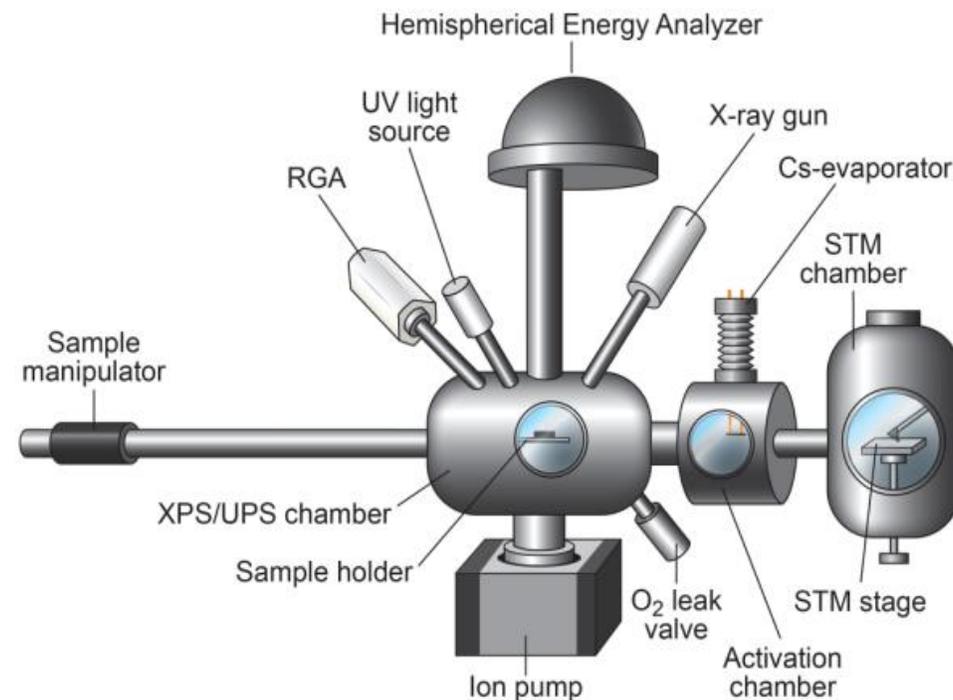
- High Quantum Efficiency (QE)
- Long charge lifetime
- High Electron Spin Polarization (ESP)

# Towards High QE GaAs Photocathode

## Substrate Preparation and Characterization



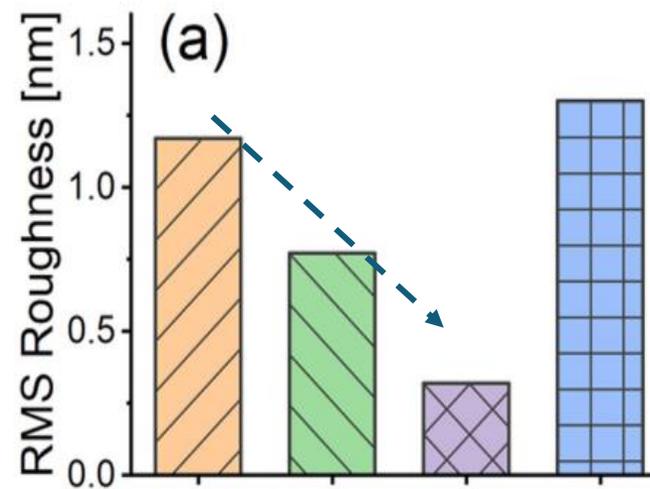
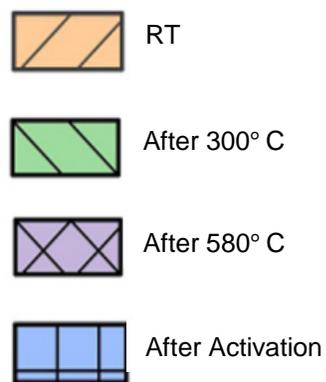
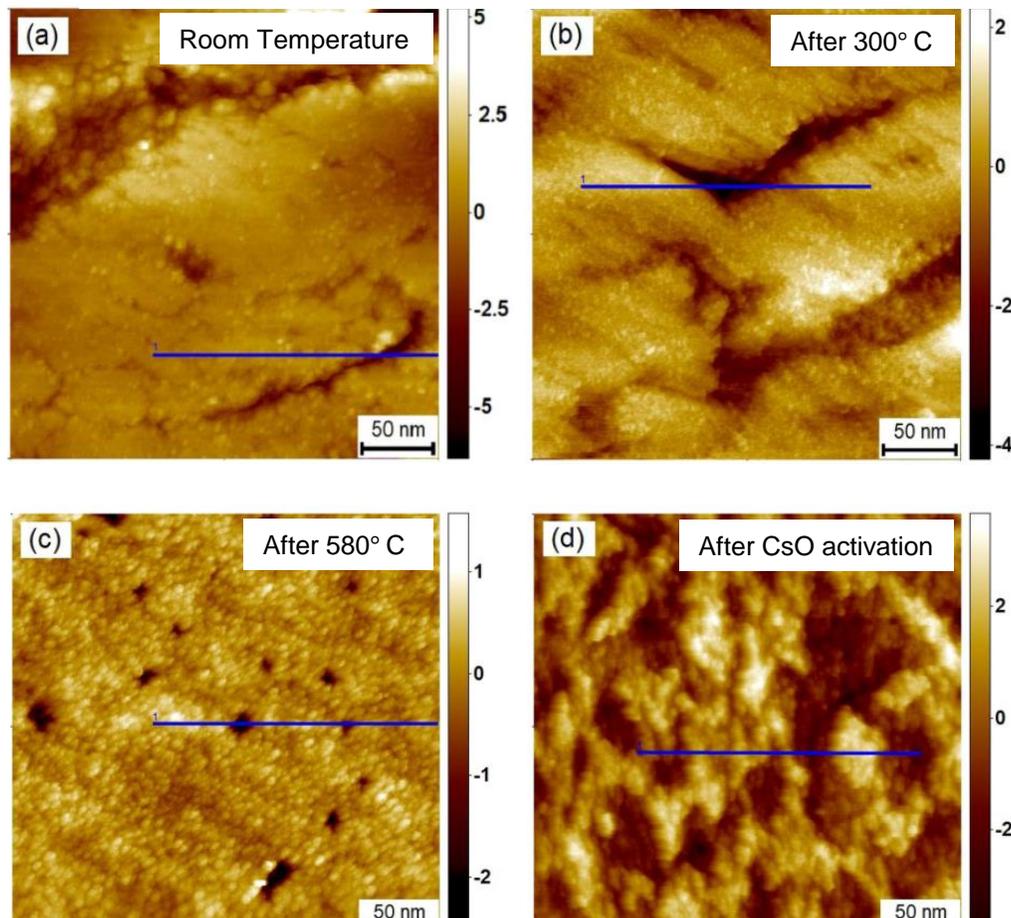
Multiprobe system located in Center for Functional Nanomaterial (CFN) at Brookhaven National Laboratory (BNL).



Schematic drawing of the multiprobe system at CFN, BNL

# Towards High QE GaAs Photocathode

## Substrate Preparation and Characterization - Surface Roughness



RMS roughness at different stage of the activation

STM - GaAs at different temperature, & after activation

# Towards High QE GaAs Photocathode

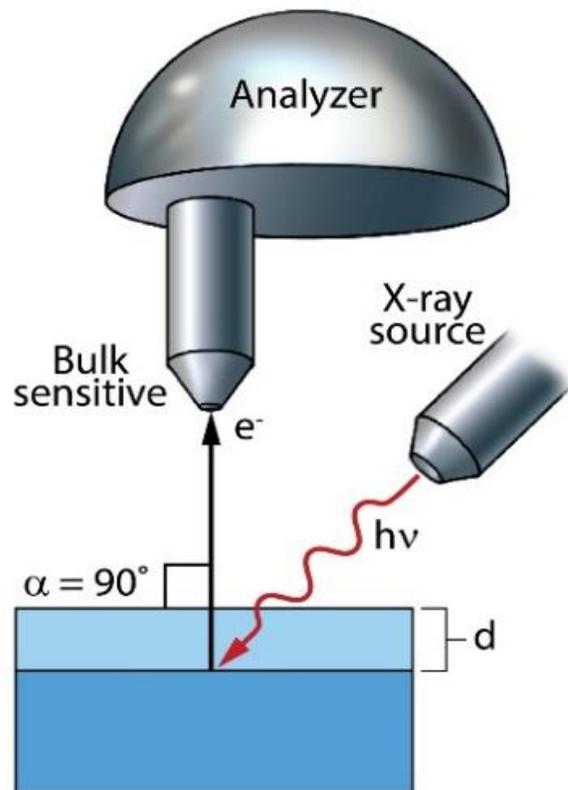
## Conclusion from Substrate Preparation and Characterization

- ❑ Contrary to common assumption, we found that right amount of heat treatment at UHV decreases the surface RMS roughness.
- ❑ This preparation is optimal for the subsequent growth of thin activation material on it.
- ❑ Reduced field emission and emittance growth.

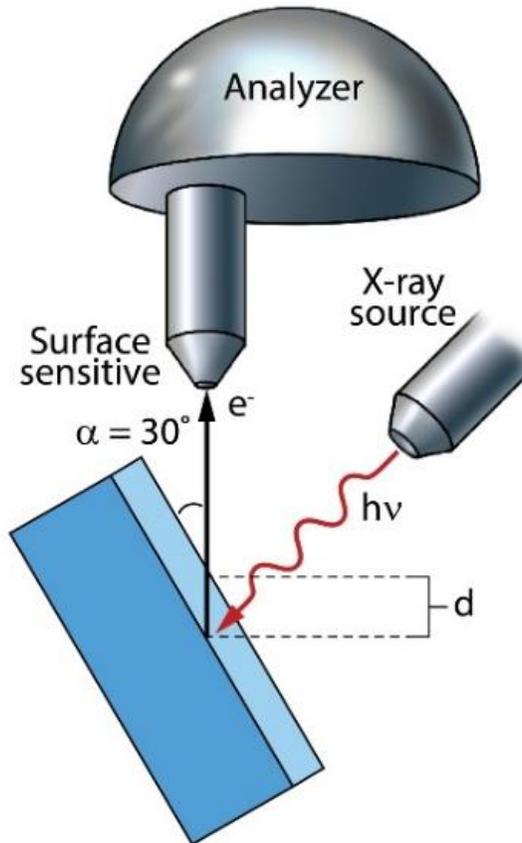
# Towards High QE GaAs Photocathode

## Chemical analysis of CsO/GaAs cathode using AR-XPS/UPS

(a) 90° take-off angle



(b) 30° take-off angle



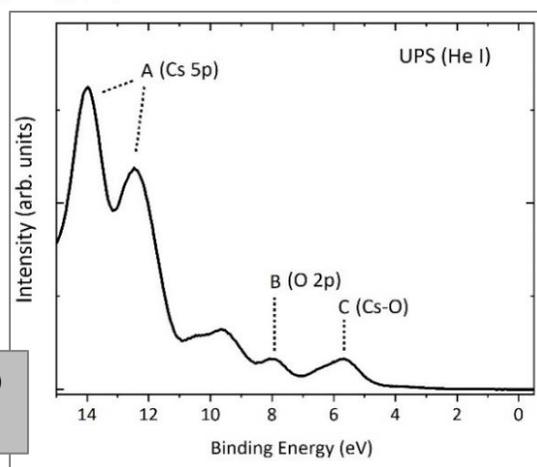
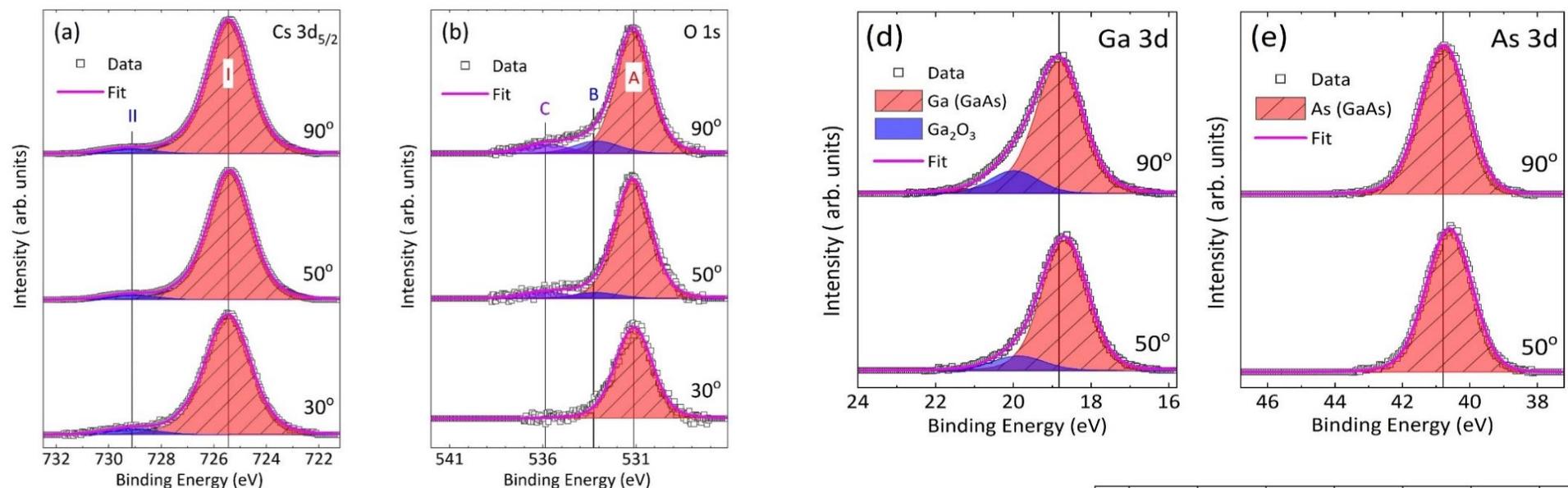
$\alpha = \text{electron take off angle}$

$ID = \text{Information depth}$

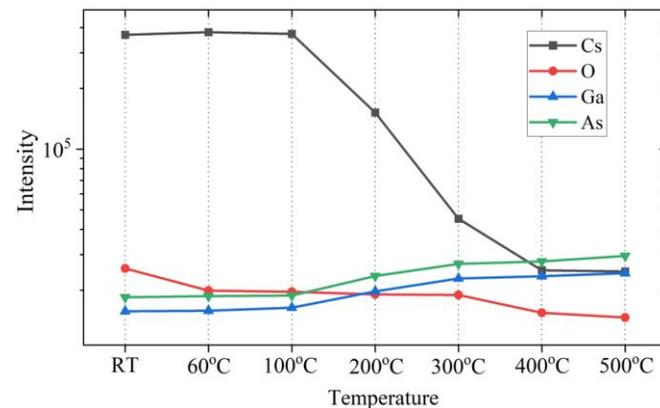
$ID = d \sin \alpha$

# Towards High QE GaAs Photocathode

## Chemical analysis of CsO/GaAs cathode using AR-XPS/UPS



UPS after Cs-O Activation



XPS - Temperature Programmed Reduction

# Towards High QE GaAs Photocathode

## Conclusion from the chemical analysis of CsO/GaAs

- ❑ This is a **first detailed chemical analysis** of Cs-O activation on GaAs.
  
- ❑ We find the ratio of Cs & O on the activation layer, **Cs:O  $\approx$  2:1**
  - **No formation of previously proposed Cs<sub>2</sub>O, or Cs<sub>11</sub>O<sub>3</sub> compound** in activation layer.
  
- ❑ XPS confirms that, surface start to lose Cs significantly at  $\sim 100^\circ\text{C}$ , whereas **oxygen loss is significant even at  $60^\circ\text{C}$** .
  - Laser illumination induced heating could destroy the cathode if temperature of the sample exceeds  $60^\circ\text{C}$ .

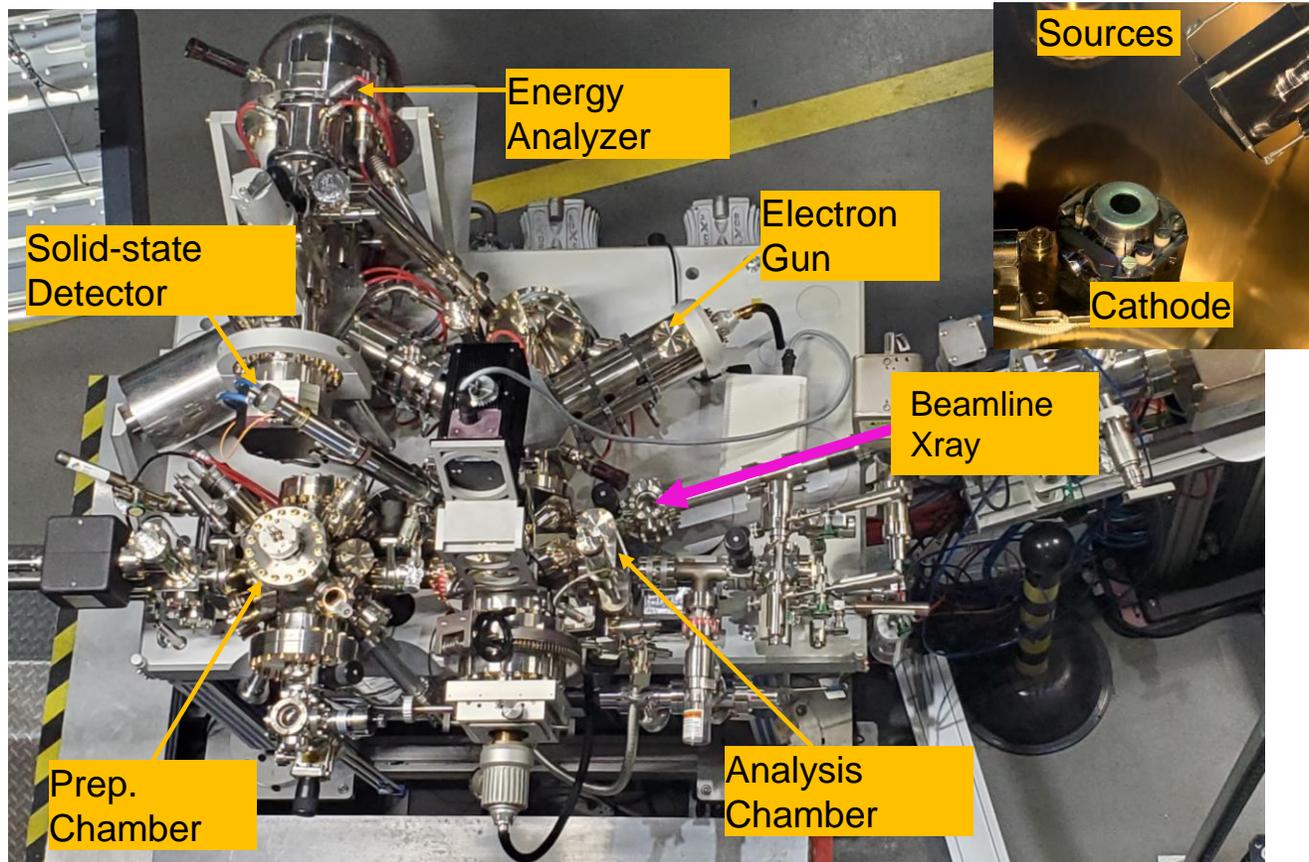
# Towards Long Charge lifetime GaAs Photocathode

## New Activation Technique using Te, Cs, and O

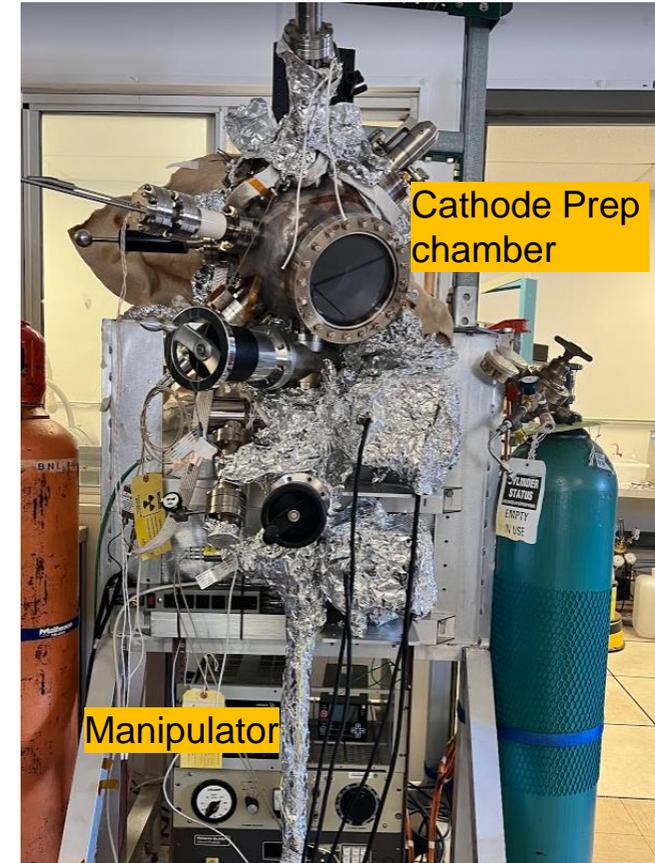
We developed a new technique of activation employing a combination of cesium, tellurium, and oxygen that shows longer charge lifetime.

# Towards Long Charge lifetime GaAs Photocathode

## New Cs-Te and Cs-Te-O based Activation on GaAs



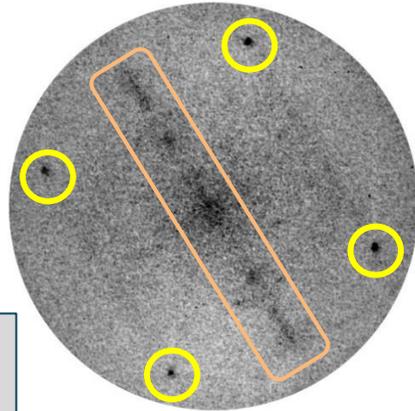
LEEM/XPEEM beamline located at NSLS II, BNL



Cathode chamber at CAD, BNL

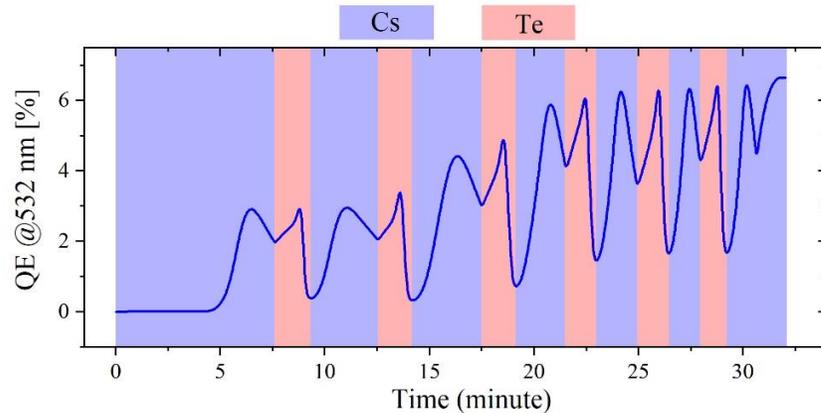
# Towards Long Charge lifetime GaAs Photocathode

## New Cs-Te and Cs-Te-O based Activation on GaAs

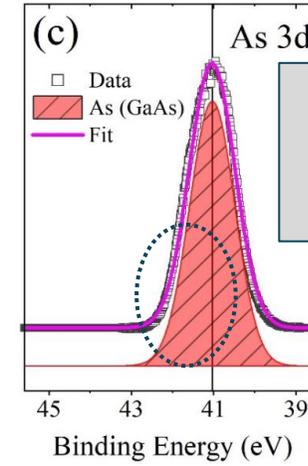
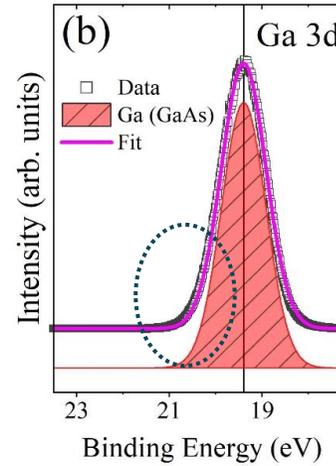


(1x1), & defused (4x6) reconstruction

Oxide desorption – LEED

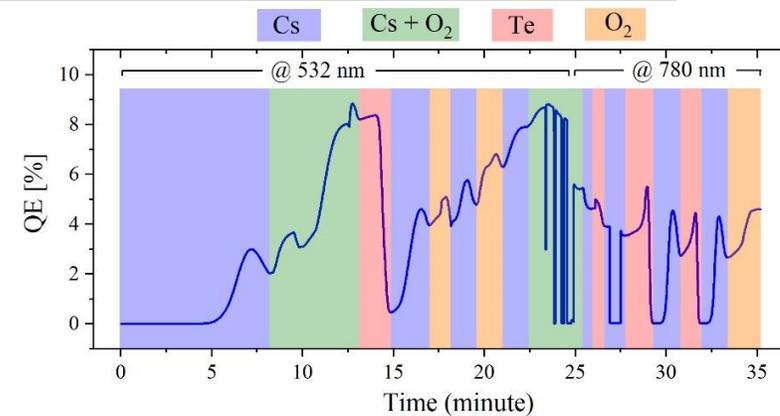


Cs-Te activation on GaAs



Oxides desorbed completely

Oxide desorption – SR-XPS



Cs-Te-O activation on GaAs

# Towards Long Charge lifetime GaAs Photocathode

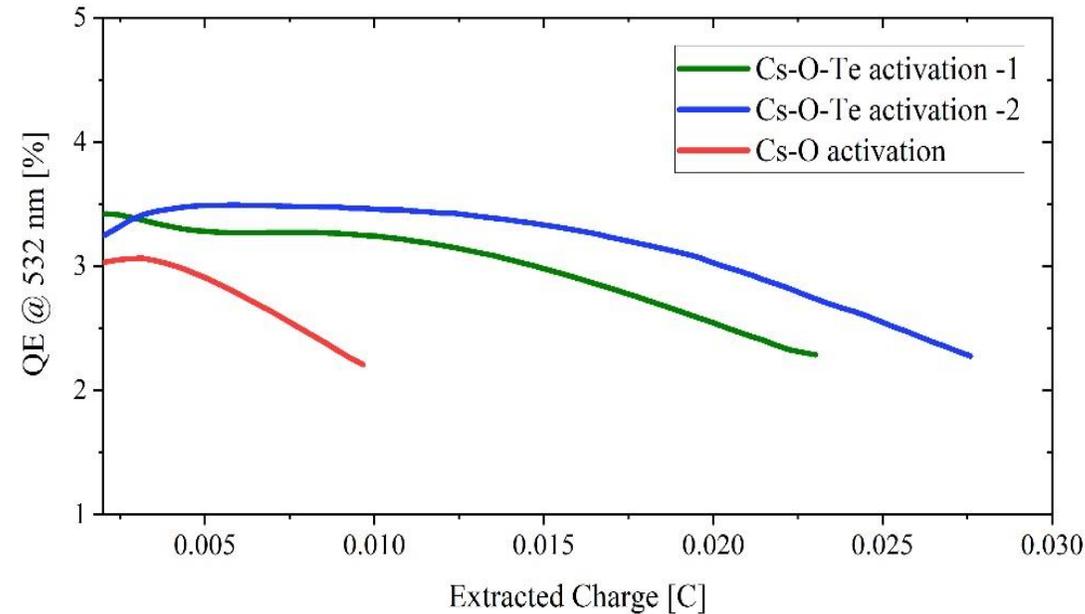
## Conclusion from the Cs-Te and Cs-Te-O based Activation

□ In Cs-Te activation QE at **532 nm: 6.6%**

□ In Cs-Te-O activation QE at **532 nm: 8.8%**; at **780 nm: 4.5%**

# Towards Long Charge lifetime GaAs Photocathode

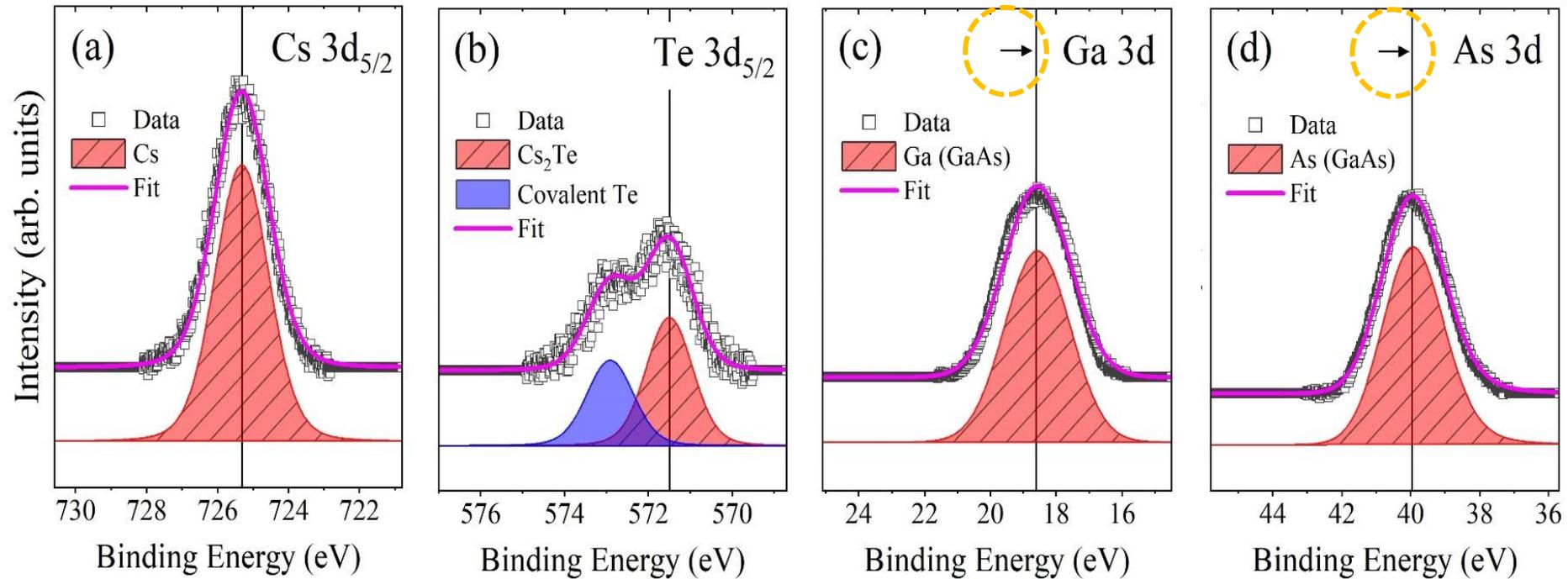
## Comparing Charge lifetime of Cs-Te-O based Activation



We demonstrated 5-6 times longer charge lifetime in a test chamber as compared to Cs-O/GaAs

# Towards Long Charge lifetime GaAs Photocathode

## Evaluating Surface Chemical States Cs-Te/GaAs



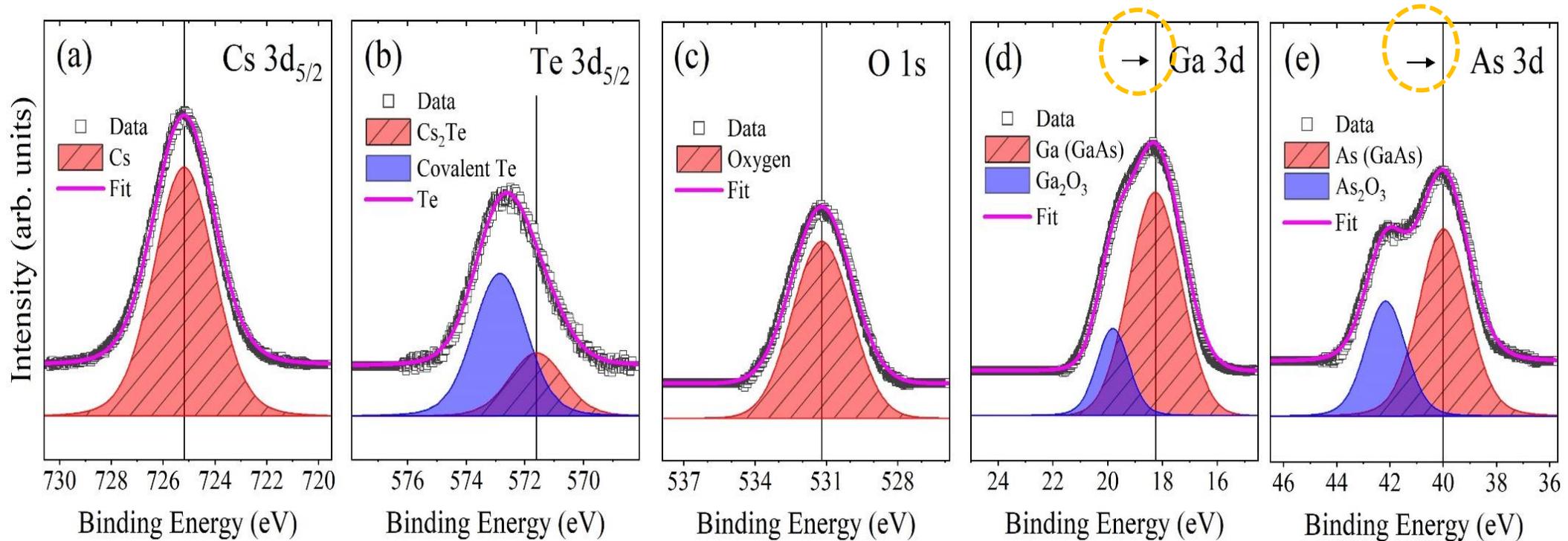
SR-XPS spectra after GaAs photocathode **activation with Cs-Te**

## Conclusion from Surface Chemical States Cs-Te/GaAs

- ❑ Successful formation of  $Cs_2Te$ , which is robust against poor vacuum
- ❑ Chemical shift of Ga 3d, & As 3d suggest formation of surface dipole, similar to Cs-O activation.
- ❑ Estimated Cs-Te layer thickness  $2 \pm 0.2 \text{ nm}$

# Towards Long Charge lifetime GaAs Photocathode

## Evaluating Surface Chemical States Cs-Te-O/GaAs



SR-XPS spectra after GaAs photocathode activation with Cs-Te-O

## Conclusion from the Chemical Analysis of Cs-Te-O/GaAs

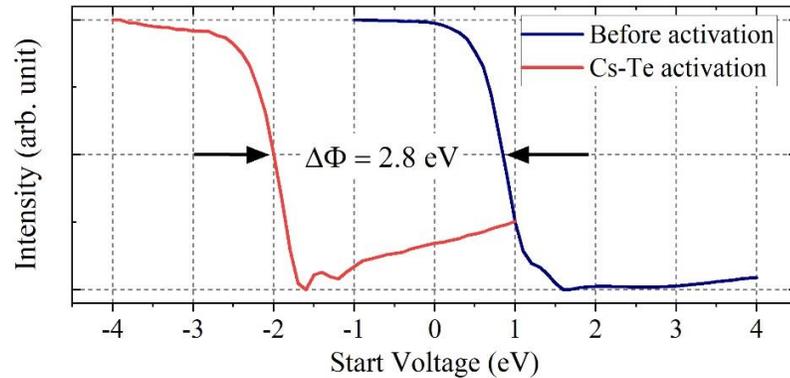
❑ Successful formation of  $Cs_2Te$ , which is robust against poor vacuum

❑ Large chemical shift of Ga 3d, & As 3d suggest formation of surface dipole similar to CsO/GaAs.

❑ Estimated Cs-Te layer thickness  $1.6 \pm 0.2 \text{ nm}$

# Towards Long Charge lifetime GaAs Photocathode

## Evaluating the Negative Electron Affinity (NEA)



LEEM I/V of Cs-Te activated GaAs

### Cs-Te/GaAs

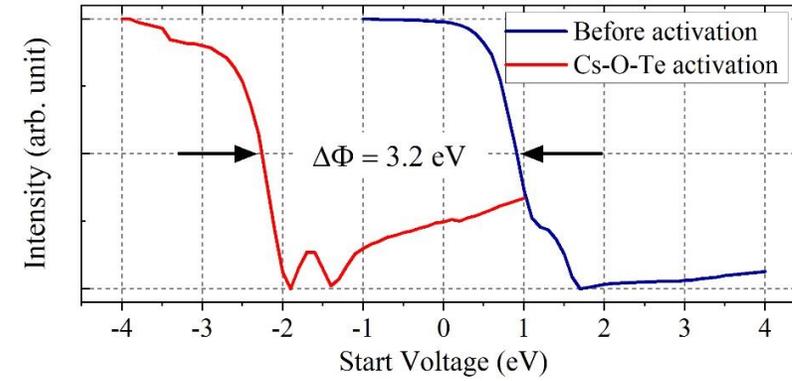
Final work function,  $\Phi_f = 1.4$  eV

Effective NEA,  $\chi_{eff} = -0.02$  eV

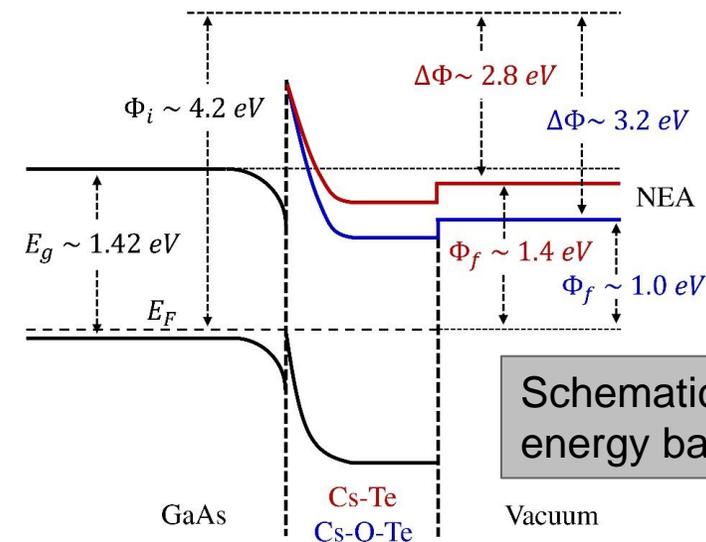
### Cs-Te-O/GaAs

Final work function,  $\Phi_f = 1.0$  eV

Effective NEA,  $\chi_{eff} = -0.42$  eV



LEEM I/V of Cs-Te-O activated GaAs



Schematic drawing of energy band diagram

## Conclusion from the NEA Measurement

□ On Cs-Te activation the achieves NEA;  $\chi_{eff} = -0.02 \text{ eV}$

□ On Cs-Te-O activation the achieved NEA;  $\chi_{eff} = -0.42 \text{ eV}$   
This is comparable to CsO/GaAs NEA.

NEA is important because the thermalized electrons at the bottom of the conduction band can escape into the vacuum. Thus, QE increases the when larger NEA is achieved.

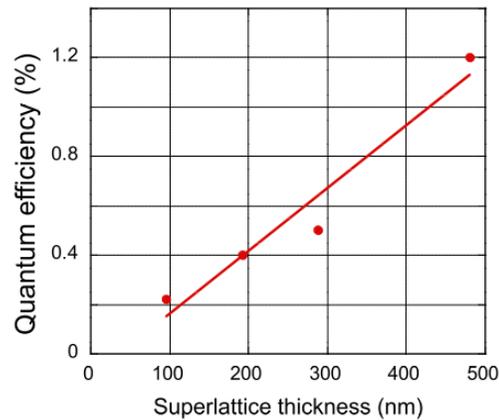
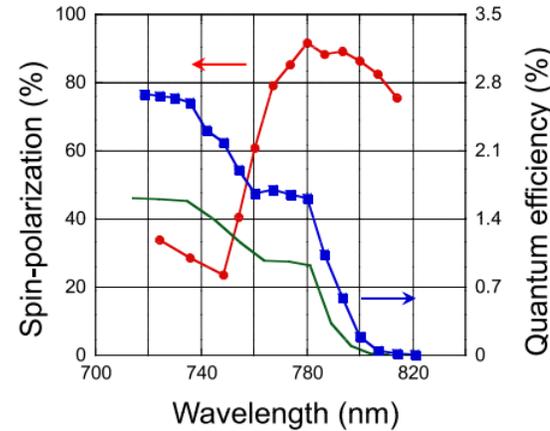
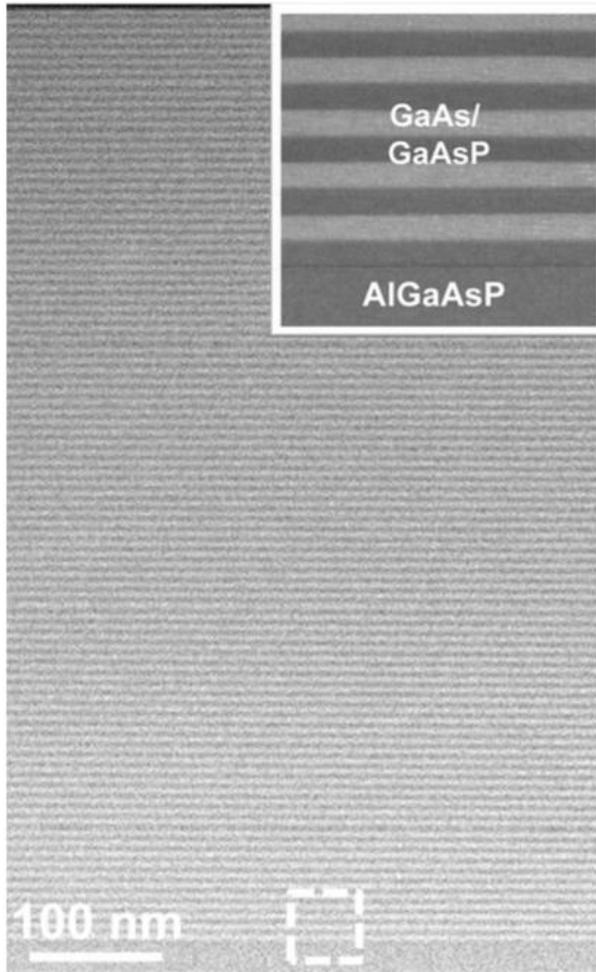
# Towards High Electron Spin Polarization (ESP)

## Motivation:

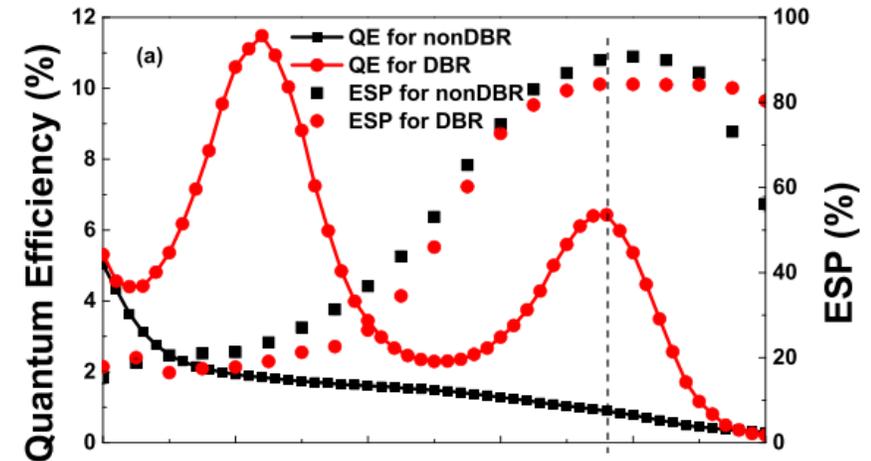
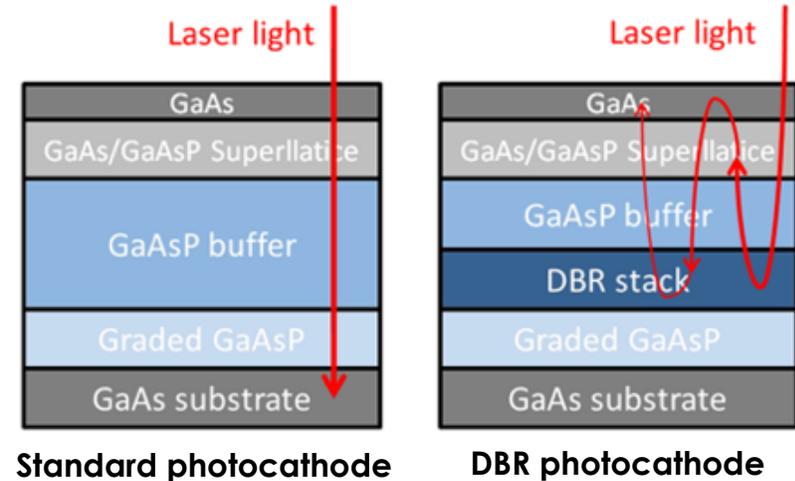
- Achieving both high QE and ESP at near bandgap energy is challenging.
- We need a stable supply of SL-GaAs

# Towards High Electron Spin Polarization (ESP)

## Superlattice (SL) GaAs



## SL – GaAs with Bragg Reflector



# Towards High QE and ESP using SL-DBR

We have been growing SL-DBR and characterizing them

➤ Details will follow in the Poster session: **WEPA68**

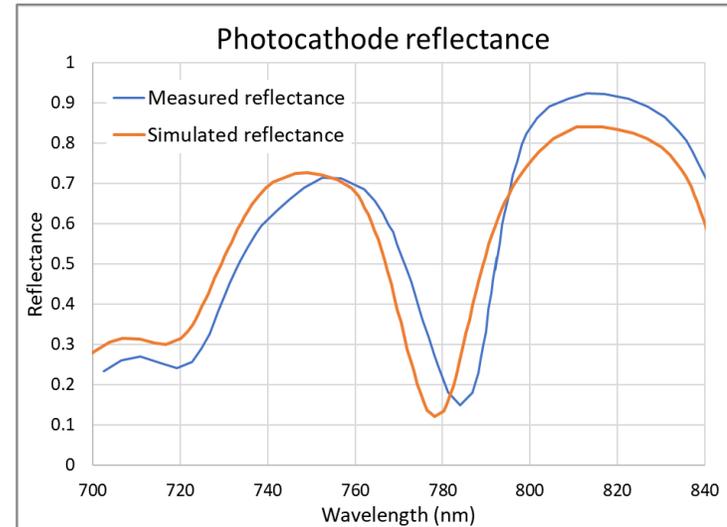


GaAs	5 nm	$p = 5 \times 10^{19} \text{ cm}^{-3}$
GaAs <sub>0.62</sub> P <sub>0.38</sub>	4 nm	$p = 5 \times 10^{17} \text{ cm}^{-3}$
GaAs	4 nm	$p = 5 \times 10^{17} \text{ cm}^{-3}$
GaAs <sub>0.81</sub> P <sub>0.19</sub>	300 nm	$p = 5 \times 10^{18} \text{ cm}^{-3}$
AlAs <sub>0.78</sub> P <sub>0.22</sub>	65 nm	$p = 5 \times 10^{18} \text{ cm}^{-3}$
GaAs <sub>0.81</sub> P <sub>0.19</sub>	55 nm	$p = 5 \times 10^{18} \text{ cm}^{-3}$
GaAs <sub>0.81</sub> P <sub>0.19</sub>	2000 nm	$p = 5 \times 10^{18} \text{ cm}^{-3}$
GaAs → GaAs <sub>0.81</sub> P <sub>0.19</sub>	2750 nm	$p = 5 \times 10^{18} \text{ cm}^{-3}$
GaAs buffer	200 nm	$p = 5 \times 10^{18} \text{ cm}^{-3}$
GaAs substrate		$p > 1 \times 10^{18} \text{ cm}^{-3}$

30 pairs

10 pairs

85 layers!!!



Good agreement between the **design** reflectance and the **measured** one.

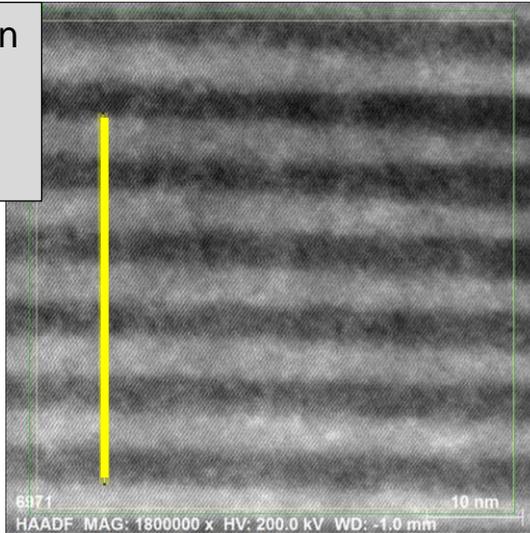
The sample **photoemission efficiency** and the **photoelectron spin polarization** are currently being evaluated at BNL

Achieved over 15% QE and ESP around 75% at near band gap photon energies.

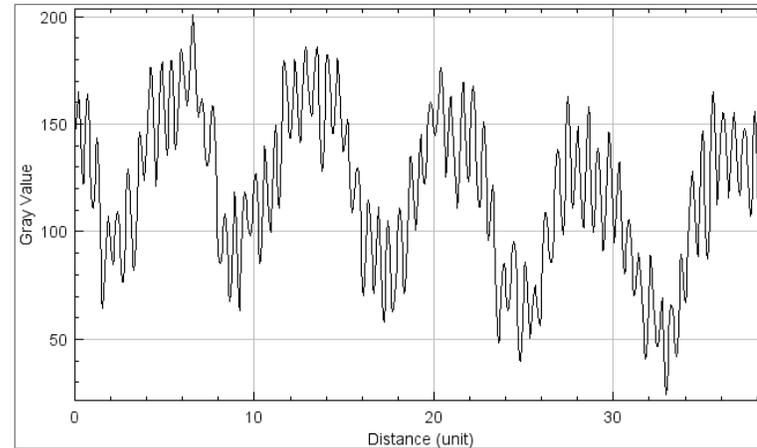
# Towards High QE and ESP using SL-DBR

## Evaluation of Crystal Quality of SL-DBR GaAs photocathode

Transmission Electron Microscopy (TEM) imaging of SL structure

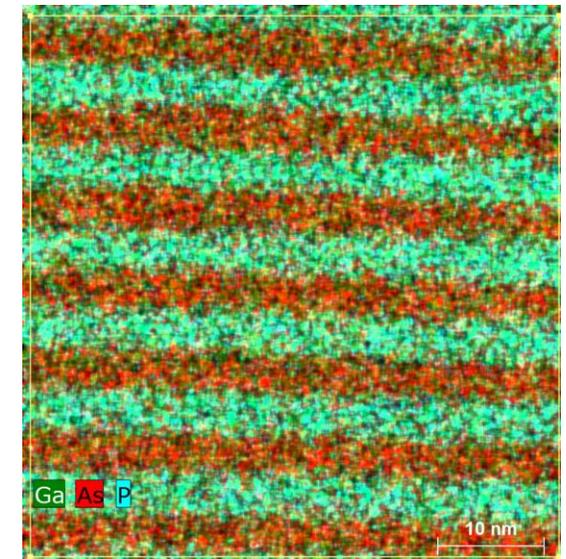
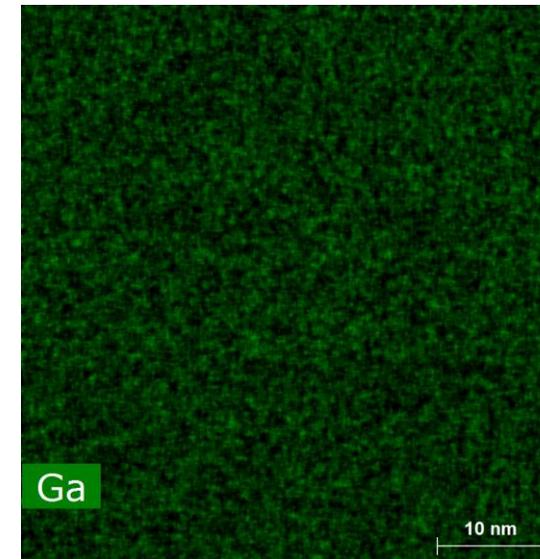
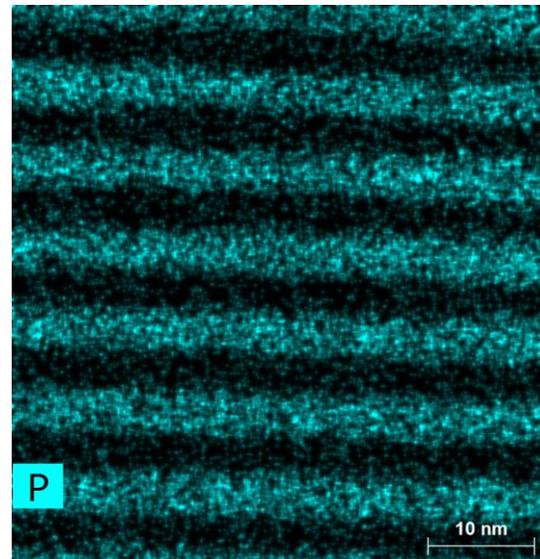
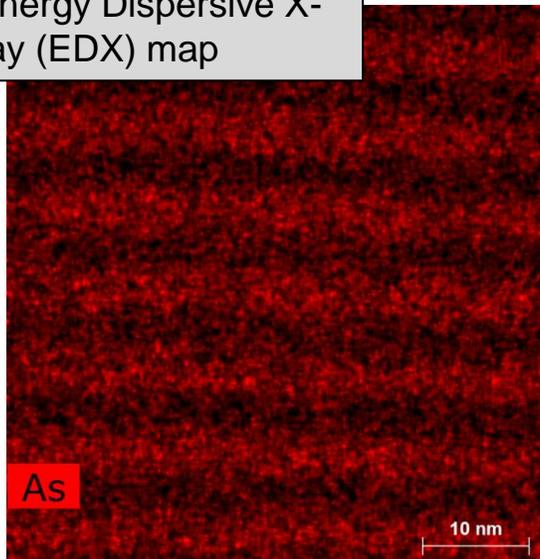


SL pair thickness:  $38.8/5 \approx 7.76$  nm



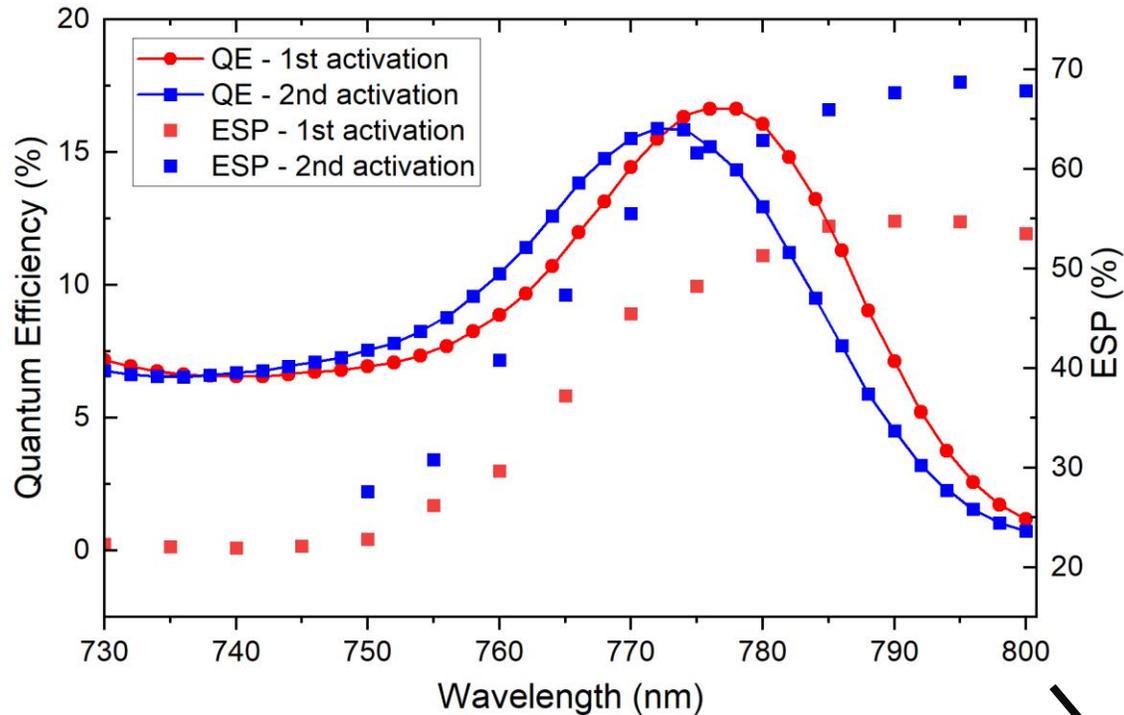
J. Biswas *et al.* NAPAC 2022, Paper WEPA68

Energy Dispersive X-ray (EDX) map

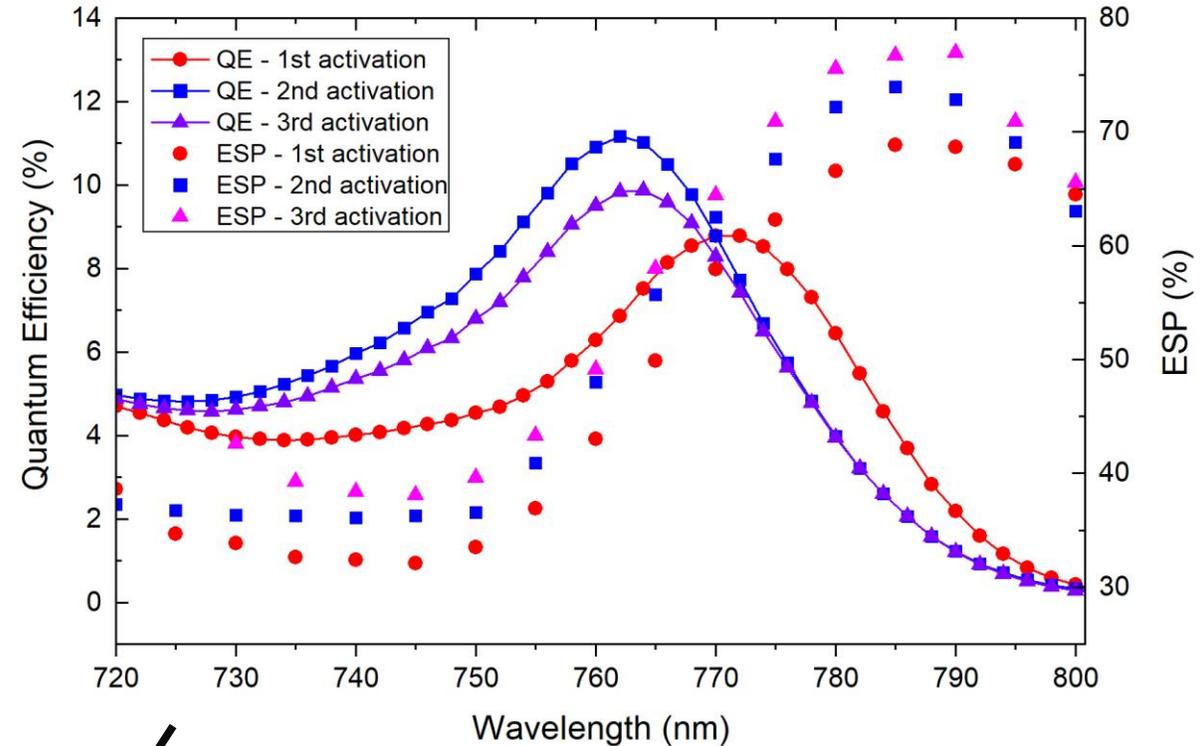


# Towards High QE and ESP using SL-DBR

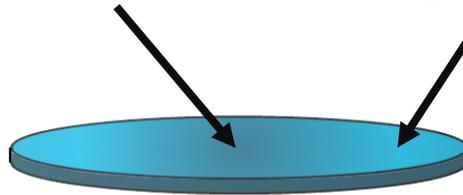
## Evaluation of QE and ESP of SL-DBR GaAs photocathode



QE ~ 16% ( ~776nm )  
ESP ~ 70% (@780nm)



QE ~ 10% ( ~765nm )  
ESP ~ 75% (@780nm)



# Summary - 1

- In the XPS measurement of the chemical states of CsO/GaAs we demonstrate the chemical states before, and after activation.
- The XPS-TPD measurement established that loss of Cs and O may take place at temperatures as low as 60°C.
- Our newly developed Cs-Te-O based activation on GaAs showed high QE, and 5-6 times longer charge lifetime compared to CsO activation in a test chamber.
- Cs-Te-O based GaAs shows NEA, and chemical states are identified for the first time.
  - Let's evaluate the robustness & charge lifetime of Cs-Te-O/GaAs in a gun
  - SL / SL-DBR with Cs-Te-O based activation

# Summary - 2

- We have been growing SL/SL-DBR GaAs and measuring the QE & ESP, crystal quality at BNL.
- On SL-DBR we obtained QE exceeding 15% and ESP close to 75% at near bandgap photon energy (i.e.,  $\sim 780 \text{ nm}$ )
  - Further tuning of SL layer, and growth method are ongoing, and activation with Cs-Te-O could lead to even higher QE.

# Thanks for your attentions!

## Questions

Acknowledge:

E. Wang, L. Cultrera, W. Liu, O. Rahman, M. Gaowei, J. Skaritka, X. Tong, J. Sadowski, K. Kisslinger, I. Ben-Zvi, T. Rao, S.D. Hawkins, S.R. Lee, J.F. Klem.